EAST Search History

L2	3	l1 and (full near exposure near system)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:29
L3	3	l1 and (full near exposure)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:29
L4	251	mask same (full near exposure)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:29
L5	31	mask same (full near exposure same system)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:30
L6	6	mask same (full near exposure near system)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:30
L7	7	mask and (full near exposure near system)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:31
L8	558	mask and (full near exposure)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:31
L9	60	mask and (full near exposure).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:31
L10	41	mask.clm. and (full near exposure).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:31
L11	7	mask.clm. and (full near exposure).clm. and mirror	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:31

EAST Search History

L12	5	mask.clm. and (full near exposure).clm. and mirror and contact	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:32
L13	2	mask.clm. and (full near exposure near system).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:33
L14	41	mask.clm. and (full near exposure).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:33
L15	25	mask.clm. same (full near exposure).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:33
L16	0	mask.clm. same (full near exposure).clm. and (lithography or lithographic) and stencil	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:34
L17	0	mask.clm. and (full near exposure).clm. and (lithography or lithographic) and stencil	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:34
L18	2	mask.clm. and (full near exposure).clm. and stencil	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:34
L19	11	mask.clm. and (full near exposure) and stencil	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:35
L20	291	mask.clm. and (exposure near2 system) and stencil	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:35
L21	52	mask.clm. and (exposure near2 system).clm. and stencil	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:35

L22	6	mask.clm. and (exposure near2 system).clm. and stencil.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:36
L23	12	(full near exposure near system)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:36
L24	24866	(exposure near system)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:36
L25	524	(exposure near system) near5 mirror	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:36
L26	12	((exposure near system) near5 mirror) and ((exposure near system) near5 contact)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:38
L27	11	((exposure near system) near10 mirror) and ((exposure near system) near10 contact) and proximity	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/18 09:38